

STN search for 10765,797

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(FILE 'HOME' ENTERED AT 08:43:25 ON 25 FEB 2005)

FILE 'CAPLUS' ENTERED AT 08:43:35 ON 25 FEB 2005

E TIMPE/AU
L1 324 S E10-15
L2 0 S L1 AND NIP
L3 1 S L1 AND MECHANISTICAL
L4 0 S NIP15
L5 3996 S NIP
L6 358 S NIP AND 15
L7 0 S L6 AND KODAK
L8 11 S L6 AND CONF?
L9 3 S L1 AND DIGITAL AND PLATE
L10 2 S L1 AND PERFLUORO?
L11 2 S L10 NOT L9
L12 0 S L1 AND DIGITAL AND PRINTING
L13 0 S L1 AND DIGITAL
L14 3 S L1 AND DIGITAL
L15 0 S L14 NOT L9
L16 3 S L14 AND PRINTING
L17 0 S L16 NOT L9
L18 2 S L14 AND (IR OR INFRARED OR INFRA RED)
L19 0 S L18 NOT L9
L20 0 S L1 AND PRITING
L21 62 S L1 AND PRINTING
L22 59 S L21 NOT L9
L23 6 S L22 AND THERMAL
L24 45 S L22 AND PHOTO?

=> log y

COST IN U.S. DOLLARS	SINCE FILE	TOTAL
	ENTRY	SESSION
FULL ESTIMATED COST	231.07	231.28
DISCOUNT AMOUNTS (FOR QUALIFYING ACCOUNTS)	SINCE FILE	TOTAL
	ENTRY	SESSION
CA SUBSCRIBER PRICE	-40.15	-40.15

STN INTERNATIONAL LOGOFF AT 08:52:12 ON 25 FEB 2005

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STN search for 10765,797

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NEWS 6 DEC 01 LISA now available on STN
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NEWS 8 DEC 15 MEDLINE update schedule for December 2004
NEWS 9 DEC 17 ELCOM reloaded; updating to resume; current-awareness
alerts (SDIs) affected
NEWS 10 DEC 17 COMPUAB reloaded; updating to resume; current-awareness
alerts (SDIs) affected
NEWS 11 DEC 17 SOLIDSTATE reloaded; updating to resume; current-awareness
alerts (SDIs) affected
NEWS 12 DEC 17 CERAB reloaded; updating to resume; current-awareness
alerts (SDIs) affected
NEWS 13 DEC 17 THREE NEW FIELDS ADDED TO IFIPAT/IFIUDB/IFICDB
NEWS 14 DEC 30 EPFULL: New patent full text database to be available on STN
NEWS 15 DEC 30 CAPLUS - PATENT COVERAGE EXPANDED
NEWS 16 JAN 03 No connect-hour charges in EPFULL during January and
February 2005
NEWS 17 FEB 25 CA/CAPLUS - Russian Agency for Patents and Trademarks
(ROSPATENT) added to list of core patent offices covered
NEWS 18 FEB 10 STN Patent Forums to be held in March 2005
NEWS 19 FEB 16 STN User Update to be held in conjunction with the 229th ACS
National Meeting on March 13, 2005
NEWS 20 FEB 28 PATDPAFULL - New display fields provide for legal status
data from INPADOC
NEWS 21 FEB 28 BABS - Current-awareness alerts (SDIs) available
NEWS 22 FEB 28 MEDLINE/LMEDLINE reloaded
NEWS 23 MAR 02 GBFULL: New full-text patent database on STN
NEWS 24 MAR 03 REGISTRY/ZREGISTRY - Sequence annotations enhanced
NEWS 25 MAR 03 MEDLINE file segment of TOXCENTER reloaded

NEWS EXPRESS JANUARY 10 CURRENT WINDOWS VERSION IS V7.01a, CURRENT
MACINTOSH VERSION IS V6.0c(ENG) AND V6.0Jc(JP),
AND CURRENT DISCOVER FILE IS DATED 10 JANUARY 2005

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NEWS WWW CAS World Wide Web Site (general information)

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* * * * * STN Columbus * * * * *

FILE 'HOME' ENTERED AT 15:47:21 ON 15 MAR 2005

=> log y

COST IN U.S. DOLLARS

SINCE FILE

TOTAL

STN search for 10765,797

	ENTRY	SESSION
FULL ESTIMATED COST	0.21	0.21

STN INTERNATIONAL LOGOFF AT 15:47:26 ON 15 MAR 2005

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TERMINAL (ENTER 1, 2, 3, OR ?):2

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NEWS	6	DEC 01	LISA now available on STN
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NEWS	8	DEC 15	MEDLINE update schedule for December 2004
NEWS	9	DEC 17	ELCOM reloaded; updating to resume; current-awareness alerts (SDIs) affected
NEWS	10	DEC 17	COMPUAB reloaded; updating to resume; current-awareness alerts (SDIs) affected
NEWS	11	DEC 17	SOLIDSTATE reloaded; updating to resume; current-awareness alerts (SDIs) affected
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NEWS	14	DEC 30	EPFULL: New patent full text database to be available on STN
NEWS	15	DEC 30	CAPLUS - PATENT COVERAGE EXPANDED
NEWS	16	JAN 03	No connect-hour charges in EPFULL during January and February 2005
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NEWS	20	FEB 28	PATDPAFULL - New display fields provide for legal status data from INPADOC
NEWS	21	FEB 28	BABS - Current-awareness alerts (SDIs) available
NEWS	22	FEB 28	MEDLINE/LMEDLINE reloaded
NEWS	23	MAR 02	GBFULL: New full-text patent database on STN
NEWS	24	MAR 03	REGISTRY/ZREGISTRY - Sequence annotations enhanced
NEWS	25	MAR 03	MEDLINE file segment of TOXCENTER reloaded
NEWS EXPRESS			JANUARY 10 CURRENT WINDOWS VERSION IS V7.01a, CURRENT MACINTOSH VERSION IS V6.0c(ENG) AND V6.0Jc(JP), AND CURRENT DISCOVER FILE IS DATED 10 JANUARY 2005

STN search for 10765,797

NEWS HOURS	STN Operating Hours Plus Help Desk Availability
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* * * * * STN Columbus * * * * *

FILE 'HOME' ENTERED AT 15:49:50 ON 15 MAR 2005

=> file caplus

COST IN U.S. DOLLARS	SINCE FILE ENTRY	TOTAL SESSION
FULL ESTIMATED COST	0.21	0.21

FILE 'CAPLUS' ENTERED AT 15:50:01 ON 15 MAR 2005

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FILE COVERS 1907 - 15 Mar 2005 VOL 142 ISS 12

FILE LAST UPDATED: 14 Mar 2005 (20050314/ED)

This file contains CAS Registry Numbers for easy and accurate substance identification.

=> s infrared or ir or infra red

232042 INFRARED

562469 IR

4681 INFRA

363053 RED

4071 INFRA RED

(INFRA(W) RED)

L1 637015 INFRARED OR IR OR INFRA RED

=> s l1 and dye

242856 DYE

L2 7711 L1 AND DYE

STN search for 10765,797

=> s l2 and fluoro?

379314 FLUORO?

L3 309 L2 AND FLUORO?

=> s l3 and perfluoro?

47229 PERFLUORO?

L4 10 L3 AND PERFLUORO?

=> s l4 not l3

L5 0 L4 NOT L3

=> s lithograph? or planograph?

43956 LITHOGRAPH?

714 PLANOGRAPH?

L6 44388 LITHOGRAPH? OR PLANOGRAPH?

=> s l6 and l3

L7 6 L6 AND L3

=> s l4 and l6

L8 0 L4 AND L6

=> d l7 all 1-6

L7 ANSWER 1 OF 6 CAPLUS COPYRIGHT 2005 ACS on STN

AN 2005:158314 CAPLUS

ED Entered STN: 24 Feb 2005

TI Polymer compositions and lithographic printing plates using them
with excellent development latitude and chemical and wear resistance

IN Nakamura, Ippei

PA Fuji Photo Film Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 82 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

IC ICM G03F007-033

ICS G03F007-00; G03F007-004; G03F007-11

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other
Reprographic Processes)

Section cross-reference(s): 38

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2005049640	A2	20050224	JP 2003-281935	20030729
PRAI	JP 2003-281935		20030729		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 2005049640	ICM	G03F007-033
	ICS	G03F007-00; G03F007-004; G03F007-11
JP 2005049640	FTERM	2H025/AA04; 2H025/AA06; 2H025/AB03; 2H025/AC08; 2H025/AD03; 2H025/CB14; 2H025/CB41; 2H025/CC11; 2H025/CC20; 2H025/DA36; 2H025/FA17; 2H096/AA06; 2H096/BA09; 2H096/EA04; 2H096/GA08

AB The compns., changing solubility to aqueous alkaline solns. by IR laser exposure, contain copolymers, bearing monomer units AZQY (A = polymerizable double bond-containing monovalent organic group; Z = single bond, divalent organic group; X = R1-4-substituted phenylene; R1-4 = H, halo, alkoxy, alkyl, aryl; Y = aminosulfonyl, OH) and onium salt-containing monomer

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units, and IR absorbers. The plates consist of supports, lower recording layers containing the copolymers, and upper recording layers containing water-insol. and alkali-soluble polymers and development inhibitors, wherein the lower and/or upper layers contain IR absorbers.

ST lithog plate IR laser exposure sensitivity; IR absorber printing plate development latitude; chem resistance lithog plate aminosulfonylphenyl polymer

IT Optical materials
(IR absorbers; lithog. printing plates containing certain copolymers bearing onium salts with good development latitude and chemical and wear resistance)

IT Dyes
(IR-absorbing, recording layer; lithog. printing plates containing certain copolymers bearing onium salts with good development latitude and chemical and wear resistance)

IT IR materials
(absorbers; lithog. printing plates containing certain copolymers bearing onium salts with good development latitude and chemical and wear resistance)

IT Phenolic resins
RL: TEM (Technical or engineered material use); USES (Uses)
(novolak, cresol-based, recording layer; lithog. printing plates containing certain copolymers bearing onium salts with good development latitude and chemical and wear resistance)

IT Lithographic plates
(presensitized; lithog. printing plates containing certain copolymers bearing onium salts with good development latitude and chemical and wear resistance)

IT Fluoropolymers
RL: TEM (Technical or engineered material use); USES (Uses)
(recording layer; lithog. printing plates containing certain copolymers bearing onium salts with good development latitude and chemical and wear resistance)

IT Polymers
RL: TEM (Technical or engineered material use); USES (Uses)
(water-insol. and alkali-soluble, upper recording layer; lithog. printing plates containing certain copolymers bearing onium salts with good development latitude and chemical and wear resistance)

IT 134127-48-3 193687-61-5
RL: TEM (Technical or engineered material use); USES (Uses)
(IR-absorbing dye, recording layer; lithog. printing plates containing certain copolymers bearing onium salts with good development latitude and chemical and wear resistance)

IT 27029-76-1, PR 54046 217651-44-0 251098-96-1 844699-05-4
844699-06-5 844699-07-6 844699-08-7 844699-09-8 844699-10-1
844699-11-2
RL: TEM (Technical or engineered material use); USES (Uses)
(recording layer; lithog. printing plates containing certain copolymers bearing onium salts with good development latitude and chemical and wear resistance)

IT 7429-90-5, Aluminum
RL: TEM (Technical or engineered material use); USES (Uses)
(support; lithog. printing plates containing certain copolymers bearing onium salts with good development latitude and chemical and wear resistance)

L7 ANSWER 2 OF 6 CAPLUS COPYRIGHT 2005 ACS on STN
AN 2004:77992 CAPLUS
DN 140:136456

STN search for 10765,797

ED Entered STN: 30 Jan 2004
TI **Lithographic** printing plates for IR laser direct
platemaking with excellent scratch resistance and development latitude
IN Miyake, Hideo
PA Fuji Photo Film Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 42 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
IC ICM G03F007-004
ICS G03F007-00
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other
Reprographic Processes)

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2004029680	A2	20040129	JP 2002-189993	20020628
PRAI	JP 2002-189993		<u>20020628</u>		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 2004029680	ICM	G03F007-004
	ICS	G03F007-00
JP 2004029680	FTERM	2H025/AA04; 2H025/AA12; 2H025/AA13; 2H025/AB03; 2H025/AC08; 2H025/AD01; 2H025/AD03; 2H025/CB52; 2H025/CC04; 2H025/CC20; 2H025/FA03; 2H025/FA17; 2H096/AA07; 2H096/AA08; 2H096/BA16; 2H096/BA20; 2H096/CA12; 2H096/EA04; 2H096/GA08

AB The plates have recording layers containing water-insol. and alkali-soluble polymers and IR absorbers on supports, wherein the layers are formed from coatings containing surfactants bearing reactive groups and F or Si elements.

ST lithog printing plate scratch resistance; printing plate recording layer reactive surfactant; fluorine surfactant plate IR development latitude

IT Optical materials
(IR absorbers; lithog. printing plates having reactive surfactant-containing recording layers with good scratch resistance and development latitude for IR laser direct platemaking)

IT IR materials
(absorbers; lithog. printing plates having reactive surfactant-containing recording layers with good scratch resistance and development latitude for IR laser direct platemaking)

IT Phenolic resins, uses
RL: TEM (Technical or engineered material use); USES (Uses)
(novolak, cresol-based, recording layer; lithog. printing plates having reactive surfactant-containing recording layers with good scratch resistance and development latitude for IR laser direct platemaking)

IT **Lithographic** plates
(presensitized; lithog. printing plates having reactive surfactant-containing recording layers with good scratch resistance and development latitude for IR laser direct platemaking)

IT **Fluoropolymers**, uses
RL: TEM (Technical or engineered material use); USES (Uses)
(reactive surfactant, recording layer; lithog. printing plates having reactive surfactant-containing recording layers with good scratch resistance and development latitude for IR laser direct platemaking)

IT Surfactants

STN search for 10765,797

(reactive; lithog. printing plates having reactive surfactant-containing recording layers with good scratch resistance and development latitude for IR laser direct platemaking)

IT 134127-48-3

RL: TEM (Technical or engineered material use); USES (Uses)

(IR-absorbing dye, recording layer; lithog.

printing plates having reactive surfactant-containing recording layers with good scratch resistance and development latitude for IR laser direct platemaking)

IT 649756-66-1 649756-67-2 649756-69-4 649756-70-7 649756-71-8

649756-73-0 649756-75-2 650609-70-4 650609-72-6

RL: TEM (Technical or engineered material use); USES (Uses)

(reactive surfactant, recording layer; lithog. printing plates having reactive surfactant-containing recording layers with good scratch resistance and development latitude for IR laser direct platemaking)

IT 58931-97-8P, Methacrylic acid-propyl methacrylate copolymer

RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(recording layer; lithog. printing plates having reactive surfactant-containing recording layers with good scratch resistance and development latitude for IR laser direct platemaking)

IT 27029-76-1, PR 54046 141634-00-6, Acrylonitrile-N-(4-aminosulfonylphenyl)methacrylamide-methyl methacrylate copolymer

RL: TEM (Technical or engineered material use); USES (Uses)

(recording layer; lithog. printing plates having reactive surfactant-containing recording layers with good scratch resistance and development latitude for IR laser direct platemaking)

L7 ANSWER 3 OF 6 CAPLUS COPYRIGHT 2005 ACS on STN

AN 2002:553400 CAPLUS

DN 137:132119

ED Entered STN: 26 Jul 2002

TI IR-sensitive direct-imaging positive-working
lithographic plate precursor

IN Oda, Akio

PA Fuji Photo Film Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 14 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

IC ICM G03F007-004

ICS G03F007-004; B41N001-14; G03F007-00; G03F007-032; G03F007-039;
G03F007-095

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2002207288	A2	20020726	JP 2001-2363	20010110
PRAI	JP 2001-2363		20010110		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 2002207288	ICM	G03F007-004
	ICS	G03F007-004; B41N001-14; G03F007-00; G03F007-032; G03F007-039; G03F007-095

AB The title lithog. plate precursor has a heat-sensitive layer, which contains a heat-sensitive water-insol. alkali solubilizable resin, an IR-absorbing dye, a F-containing polymer, on a hydrophilic

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Priority
heats

STN search for 10765,797

support, wherein the heat-sensitive layer contains ≥ 1.4 % F-containing polymer based on the total solid component and has ≤ 1.4 g/cm² coating amount The lithog. plate precursor shows the wide development latitude.

ST IR sensitive imaging pos working lithog plate precursor

IT Lithographic plates

(IR-sensitive direct-imaging pos.-working lithog. plate precursor)

IT Fluoropolymers, uses

RL: TEM (Technical or engineered material use); USES (Uses)
(fluoropolymer for IR-sensitive direct-imaging pos.-working lithog. plate precursor)

IT 115515-73-6, Defensa MCF 312 137462-24-9, Megafac F 176

RL: TEM (Technical or engineered material use); USES (Uses)
(fluoropolymer for IR-sensitive direct-imaging pos.-working lithog. plate precursor)

L7 ANSWER 4 OF 6 CAPLUS COPYRIGHT 2005 ACS on STN

AN 2001:778174 CAPLUS

DN 135:325292

ED Entered STN: 26 Oct 2001

TI Near-IR-sensitive positive photoimaging materials and presensitized lithographic plates therefrom

IN Urano, Toshiyoshi; Minakami, Junji

PA Mitsubishi Chemical Corp., Japan

SO Jpn. Kokai Tokkyo Koho, 16 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

IC ICM G03F007-004

ICS B41N001-14; G03F007-00

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

Section cross-reference(s): 38, 41

FAN.CNT 1

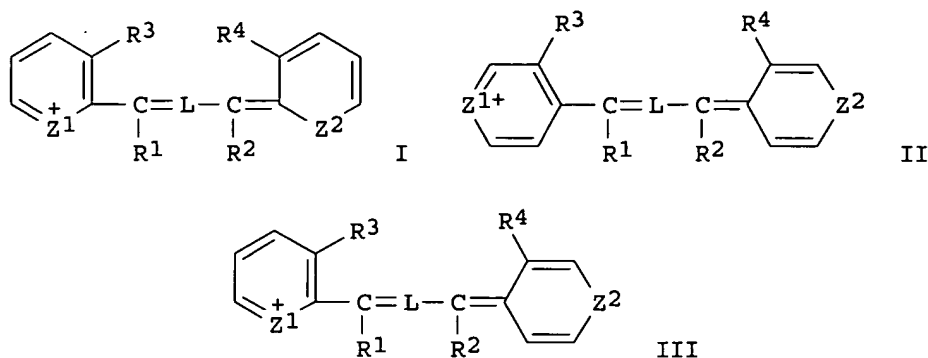
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2001296652	A2	<u>20011026</u>	JP 2000-113118	20000414
PRAI	JP 2000-113118		20000414		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 2001296652	ICM	G03F007-004
	ICS	B41N001-14; G03F007-00

OS MARPAT 135:325292

GI



- AB The materials, showing high solvent solubility and offering high-contrast patterns, comprise alkali-soluble resins and near-IR-absorbing dyes composed of (thio)pyrylium cations and **fluoroarylboride** anions. The cations may be represented by I-III [Z1, Z2 = O, S; R1-4 = H, alkyl; L = (un)substituted mono-, tri-, penta-, or heptamethine bridge].
- ST thiopyrylium pyrylium IR dye pos photoimaging;
pyrylium **fluoroarylboride** IR dye pos
photoimaging; lithog master pyrylium IR absorbing dye;
solvent soly pattern contrast pyrylium photoimaging
- IT Dyes
(IR-absorbing, near-IR; near-IR-sensitive
pos. photoimaging materials containing sp. (thio)pyrylium dyes for lithog.
platemaking)
- IT Phenolic resins, uses
RL: DEV (Device component use); TEM (Technical or engineered material
use); USES (Uses)
(novolak, cresol-based; near-IR-sensitive pos. photoimaging
materials containing sp. (thio)pyrylium dyes for lithog. platemaking)
- IT Photoimaging materials
(pos., near-IR-sensitive; near-IR-sensitive pos.
photoimaging materials containing sp. (thio)pyrylium dyes for lithog.
platemaking)
- IT **Lithographic** plates
(presensitized; near-IR-sensitive pos. photoimaging materials
containing sp. (thio)pyrylium dyes for lithog. platemaking)
- IT 368421-31-2 368421-32-3
RL: CAT (Catalyst use); USES (Uses)
(light-heat-converting layers; near-IR-sensitive pos.
photoimaging materials containing sp. (thio)pyrylium dyes for lithog.
platemaking)
- IT 27029-76-1, m-Cresol-p-cresol-formaldehyde copolymer 367953-19-3
RL: DEV (Device component use); TEM (Technical or engineered material
use); USES (Uses)
(light-heat-converting layers; near-IR-sensitive pos.
photoimaging materials containing sp. (thio)pyrylium dyes for lithog.
platemaking)
- L7 ANSWER 5 OF 6 CAPLUS COPYRIGHT 2005 ACS on STN
- AN 2001:472601 CAPLUS
- DN 135:84326
- ED Entered STN: 29 Jun 2001
- TI Thermal digital **lithographic** printing plate
- IN Patel, Jayanti; Saraiya, Shashikant; Hauck, Celin-Savariar; Huang,

STN search for 10765,797

Jianbing; Mikell, Frederic; Shimazu, Kenichi; Merchant, Nishith
PA Kodak Polychrome Graphics Company Ltd., USA
SO PCT Int. Appl., 39 pp.
CODEN: PIXXD2
DT Patent
LA English
IC ~~ICM~~ B41M005-00
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other
Reprographic Processes)

FAN.CNT 6

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	WO 2001045958	A2	20010628	WO 2000-US42759	20001212
	WO 2001045958	A3	20020131		
	W: BR, JP				
	RW: AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE, TR				
	US 6352811	B1	20020305	US 1999-469490	19991222
	BR 2000016716	A	20020903	BR 2000-16716	20001212
	EP 1263590	A2	20021211	EP 2000-992907	20001212
	R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, FI, CY, TR				
	JP 2003518264	T2	20030603	JP 2001-546484	20001212
PRAI	US 1999-469490	A	19991222		
	US 1998-90300P	P	19980623		
	US 1999-301866	A2	19990429		
	WO 2000-US42759	W	20001212		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
WO 2001045958	ICM	B41M005-00
US 6352811	ECLA	B41C001/10A

AB The invention relates to thermal lithog. plates that are imaged with an IR laser and processed with an aqueous alkaline developer. The thermal imaging element is made up of a substrate and a composite layer structure composed of 2 layer coatings. Preferably, the 1st layer of the composite is composed of an aqueous developable polymer mixture containing a solubility inhibiting

material and a photothermal conversion material which is contiguous to the hydrophilic substrate. The 2nd layer of the composite is insol. in the aqueous solution, is ink receptive, and is composed of ≥ 1 nonaq. soluble polymers which are soluble or dispersible in a solvent which does not dissolve the 1st layer. The 2nd layer may also contain a photothermal conversion material. Alternatively, the composite layer may be free of photothermal conversion material when thermal imaging is carried out using a thermal printing head.

ST thermal digital lithog printing plate acrylic binder resin urethane

IT IR lasers

Lithographic plates

Thermal printing materials

(IR-sensitive thermal lithog. plate containing acrylic binder resin and carbonyl-containing solubility inhibitor)

IT Polyurethanes, uses

RL: DEV (Device component use); MOA (Modifier or additive use); NUU (Other use, unclassified); POF (Polymer in formulation); USES (Uses)

(IR-sensitive thermal lithog. plate containing acrylic binder resin and carbonyl-containing solubility inhibitor)

IT **Fluoropolymers**, uses

RL: DEV (Device component use); MOA (Modifier or additive use); NUU (Other use, unclassified); POF (Polymer in formulation); USES (Uses)

STN search for 10765,797

(MP 1100; coating for thermal digital lithog. printing plate containing)
IT Phenolic resins, uses
RL: DEV (Device component use); MOA (Modifier or additive use); NUU (Other use, unclassified); POF (Polymer in formulation); USES (Uses)
(novolak; IR-sensitive thermal lithog. plate containing acrylic binder resin and carbonyl-containing solubility inhibitor)
IT Acrylic polymers, uses
RL: DEV (Device component use); MOA (Modifier or additive use); NUU (Other use, unclassified); POF (Polymer in formulation); USES (Uses)
(polyester-; IR-sensitive thermal lithog. plate containing acrylic binder resin and carbonyl-containing solubility inhibitor)
IT Recording materials
(thermal; IR-sensitive thermal lithog. plate containing acrylic binder resin and carbonyl-containing solubility inhibitor)
IT 9002-84-0, MP 1100
RL: DEV (Device component use); MOA (Modifier or additive use); NUU (Other use, unclassified); POF (Polymer in formulation); USES (Uses)
(MP 1100; coating for thermal digital lithog. printing plate containing)
IT 2390-60-5, Victoria Blue BO 5496-71-9, ADS 1060A 9004-70-0, E 950
9011-14-7, PMMA 59269-51-1, Poly(vinyl phenol) 134127-48-3, ADS 830A
199444-11-6, KF 654B-PINA
RL: DEV (Device component use); MOA (Modifier or additive use); NUU (Other use, unclassified); POF (Polymer in formulation); USES (Uses)
(coating for thermal digital lithog. printing plate containing)
IT 346593-65-5, PC-T 153 346594-06-7, JK 5
RL: DEV (Device component use); NUU (Other use, unclassified); RCT (Reactant); RACT (Reactant or reagent); USES (Uses)
(developer for thermal digital lithog. printing plate containing)
IT 634-21-9 212964-63-1
RL: NUU (Other use, unclassified); RCT (Reactant); RACT (Reactant or reagent); USES (Uses)
(solubility-inhibitor dye; coating for thermal digital lithog. printing plate containing)
IT 346587-45-9P 346587-46-0P 346587-47-1P 346587-48-2P 346587-50-6P
346587-52-8P
RL: DEV (Device component use); PNU (Preparation, unclassified); POF (Polymer in formulation); SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(synthesis of acrylic binder resin free of carboxyl group for thermal digital lithog. printing plate)

L7 ANSWER 6 OF 6 CAPLUS COPYRIGHT 2005 ACS on STN

AN 1985:496431 CAPLUS

DN 103:96431

ED Entered STN: 22 Sep 1985

TI Highly photosensitive aqueous solvent-developable printing assembly

IN Herbert, Alan J.

PA Minnesota Mining and Manufacturing Co., USA

SO U.S., 9 pp.

CODEN: USXXAM

DT Patent

LA English

IC ICM G03G013-28

NCL 430049000

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	US 4521503	A	19850604	US 1984-609286	19840511

STN search for 10765,797

EP 161870	A2	19851121	EP 1985-303104	19850501
EP 161870	A3	19870923		
EP 161870	B1	19901219		

R: BE, DE, FR, GB, IT

JP 60244952	A2	19851204	JP 1985-98883	19850509
PRAI US 1984-609286	A	19840511		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
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US 4521503	ICM	G03G013-28
	NCL	430049000

AB A photoimaging assembly useful for preparation of lithog. plates and printed circuits consists of (1) an electroconductive support, (2) a photoresist layer sensitive to light at 250-450 nm region, and (3) a photoconductive upper layer containing spectrally sensitized Zn oxide sensitive to 370-1200 nm range in H2O-soluble or H2O-dispersible binder. Thus, an Al support (silicated and primed) was coated with a 8 weight% solids composition containing

poly(alkyl orthophthalate) prepolymer, poly(vinylpyrrolidone), pentaerythritol tetraacrylate, cellulose acetate butyrate, polyurethane, 2-(p-methoxystyryl)-4,6-bis(trichloromethyl)-s-triazine, paraformaldehyde-p-diazodiphenylamine copolymer fluoroborate salt, yellow oil soluble dye dispersion, Microlith Blue 4 GK, MeCOEt, DMF, ethylene glycol monomethyl ether, air dried, overcoated with a dispersion containing EtOH, poly(vinylpyrrolidone), Photox 80 IR -125, dried, corona-discharged, IR imagewise exposed, developed with Scott System 200 toner, exposed in Colite arc frame, and developed with H2O.

ST printing plate photoimaging assembly; photoconductor photoresist imaging structure; elec circuit photoconductor photoresist structure

IT Photoimaging compositions and processes
(photosensitive assembly containing electroconductive support and photoresist layer and photoconductive upper layer containing spectrally sensitized zinc oxide for)

IT Electric circuits
Lithographic plates
(photosensitive imaging assembly for preparation of, containing electroconductive support and photoresist layer and photoconductive upper layer containing spectrally sensitized zinc oxide)

IT 115-39-9 9003-39-8 9003-53-6 9003-54-7 9004-64-2 9010-76-8
9011-14-7 54957-10-7

RL: USES (Uses)

(photoimaging assembly containing electroconductive support and photoresist layer and photoconductive zinc oxide layer containing, for preparation of lithog. plates and printed circuits)

IT 1314-13-2, uses and miscellaneous

RL: USES (Uses)

(photoimaging assembly containing electroconductive support and photoresist layer and top layer containing, for preparation of lithog. plates and

printed
circuits)

IT 101-68-8D, reaction products with diols 147-14-8 4986-89-4 9003-39-8
42573-57-9 56646-84-5 62428-08-4 67290-46-4 69220-42-4

RL: USES (Uses)

(photoimaging assembly containing electroconductive support and photoresist layer containing, and photoconductive top layer, for fabrication of lithog. plates and printed circuits)

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